CONTENTS

The research deals with problem of optimization of "sacrificial" polyimide layer etching process in manufacture of Microsystems on the basis of multilevel patterns. It is determined, that the physicochemical modification of thin polyimide films and coatings by plasma-chemical hexamettyledisilazane vapor treatment propagates through to all their thickness, changing their bond character, surface and bulk properties and nature of interphase interaction.

Deflection of thin diaphragms of the circular, square, triangular and hexagonal forms with clamped edges under various loads is studied. This research is limited to deflection $W \leq h$. It is shown, that, changing the sizes diaphragms MMS, it is possible to change a parity effective rigidity and maximal deflections of diaphragms of the different form. Is established, that in nonlinear approach under influence of an electrical field the size of a critical deflection of diaphragms is determined not only initial gap between electrodes, but also thickness of diaphragms.

Modeling of radiation distribution inside thin dielectric layer based in near wave zone of small source has been carried out. Nearfield radiation is considered to be the second waves emmited by mesoscopic dielectric object which interacts with external electromagnetic wave. Theoretical model is bassed on the integral equations obtained from Maxwell equiations by Green's function method. Numerical results are obtained in unretardation approach due to the fact that all distances in question system are much smaller than wave length of the external field. It was shown that the distribution of electric field intensity in the layer can notably depend on the field com-

ponents which are perpendicular to surfaces of the layer. It takes place even when these components are absent in the external waves.

The basic methodical and technical approaches for investigation of grain-structure evolution of nano- and microcrystalline materials using atomic-forced microscopy have been developed. In particular, structure evolution of Al—Mg—Sc—Zr and Al—Zn—Mg—Sc—Zr alloys produced by equal channel angular pressing has been studied. As a preliminary treatment, the samples of Al—Mg—Sc—Zr and Al—Zn—Mg—Sc—Zr alloys were exposed to heat treatments (annealings) and superplastic deformation.

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New topographic and spectroscopic phenomena due to weak exchange interaction of carbon atoms of different low-dimensional nanosystems (point defects, ensembles of ordered nanotubes on graphite, Moire patterns) are found and explained.

Analytical survey of VLSI systems and design methodology literature is proposed in this paper. The design systems evolution forecast is made. They will progress in direction of design flows consolidation between systems on circuit boards and systems on chips based on standard Macroblocks (IP-blocks) using.

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Possible approaches to built-in self-testing (BIST) of microprocessors are discussed. Micro Program Stimuli Source BIST method (MSS BIST) is presented. Possible applications of the method for non-microprogram controlled IPs (FSM-bassed) are discussed. The MSS BIST method combined with method of simulating of external environment provides high fault coverage percentage and small hardware overhead.

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